

In re: *Kong et al.*
Appl. Serial No. 09/715,576
Filed: November 17, 2000
Page 2

Listing of Claims:

22 (previously presented): A chemical vapor deposition system according to Claim 49 wherein said reaction vessel is made of quartz.

24 (previously presented): A chemical vapor deposition system according to Claim 49 wherein said source of electromagnetic radiation comprises an induction coil surrounding said reaction vessel.

49 (currently amended): A chemical vapor deposition system consisting essentially of:

a reactor vessel formed of a material substantially transparent to electromagnetic radiation;

a gas supply system in fluid communication with said reactor vessel;

a source of electromagnetic radiation external to said reaction vessel; and

a susceptor within said reaction vessel, and said susceptor formed of a material that is thermally responsive to electromagnetic radiation, wherein said susceptor ~~being an inverted truncated cone~~ is defined by a plurality of adjacent straight sidewall sections forming a hollow inverted truncated cone with ~~and~~ a plurality of wafer pockets on the inner circumference of said truncated cone, with and wherein the spacing between facing ~~walls~~ sidewall sections is unobstructed and so dimensioned that being small enough for said facing walls sidewall sections to radiantly heat the exposed free surface of a facing substrate wafer to substantially the same temperature as said susceptor portion heats a substrate wafer that is in one of said wafer pockets to thereby minimize or substantially eliminate radial and axial temperature gradients across a substrate wafer.

50 (previously presented): A chemical vapor deposition system according to Claim 49 wherein said susceptor is formed from graphite coated with silicon carbide.